

**Search Notes**

Application/Control No.

09/484,303

Examiner

W. David Coleman

Applicant(s)/Patent under  
Reexamination

AHN ET AL.

Art Unit

2823

**SEARCHED**

Class	Subclass	Date	Examiner
438	643 686 627	4/26/05	WDC
438	650	1	1

**INTERFERENCE SEARCHED**

Class	Subclass	Date	Examiner
438	643	4/26/2005	WDC

**SEARCH NOTES  
(INCLUDING SEARCH STRATEGY)**

	DATE	EXMR
EAST 2.0.1 Applicant forms a single diffusion barrier after forming a conductive plug and then covers the barrier with cont.	4/26/2005	WDC
a conductive line for metallization of an integrated circuit.	4/26/2005	WDC